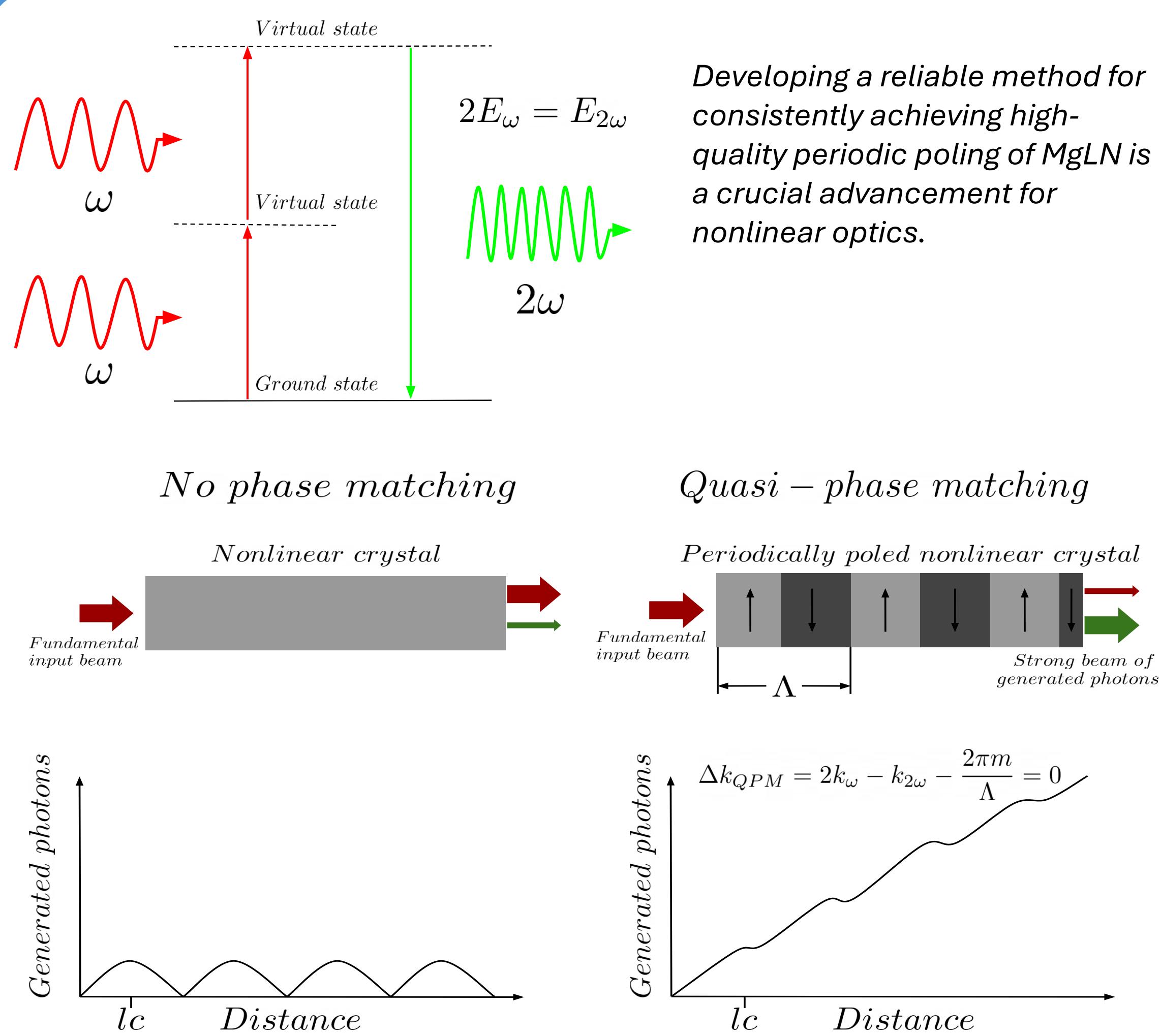


Periodic polarisation of MgO-doped lithium niobate

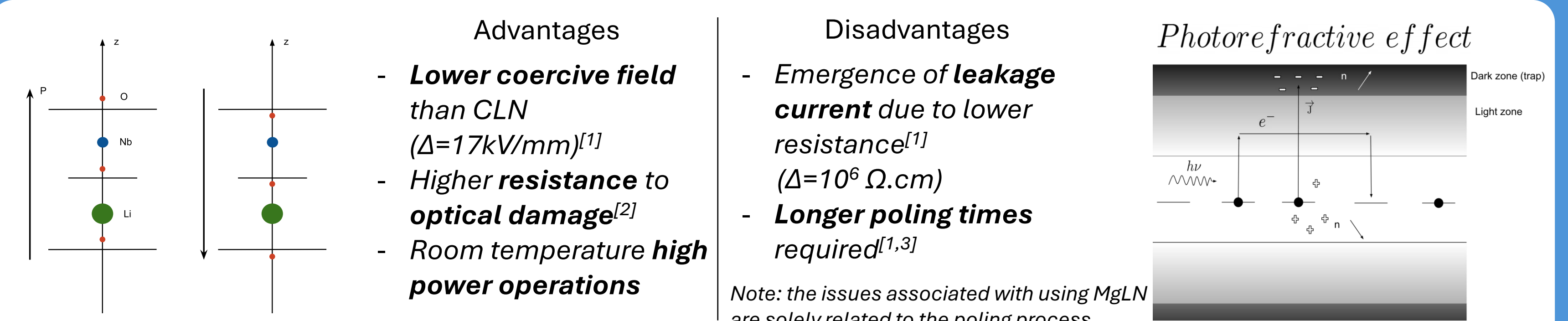
Abstract

Emerging quantum communication applications drive the rapid development of upconversion single-photon detectors and entangled photon-pair sources, both of which rely on frequency conversion in periodically poled lithium niobate (PPLN) waveguides as their core components. MgO-doped congruent lithium niobate (MgLN) is recognized as the most promising material for fabricating PPLN due to its attractive properties. However, leakage current complicates the high-quality periodic poling of MgLN, especially when using the technique with liquid electrodes. In this study, we investigate the poling properties of MgLN and describe the modifications made to an existing experimental setup and protocol for PPLN production to meet the requirements of PPMgLN manufacturing.

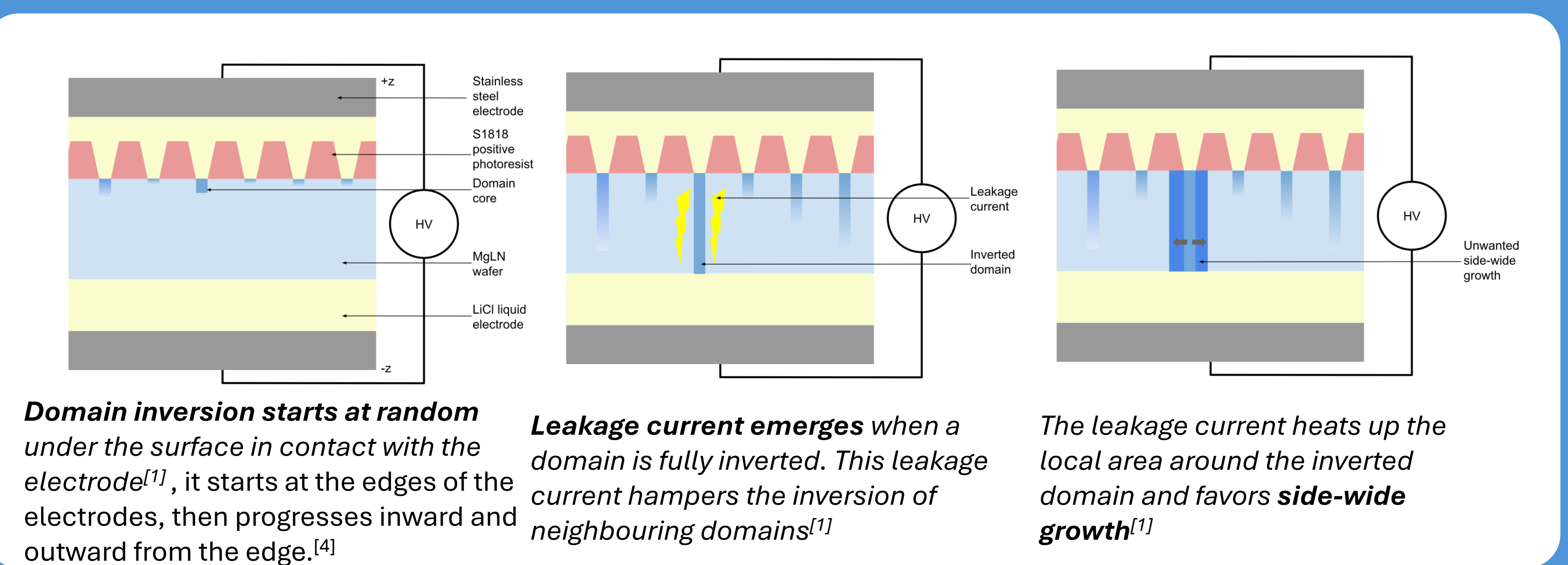
1. Quasi-phase matching (QPM) and second harmonic generation (SHG)



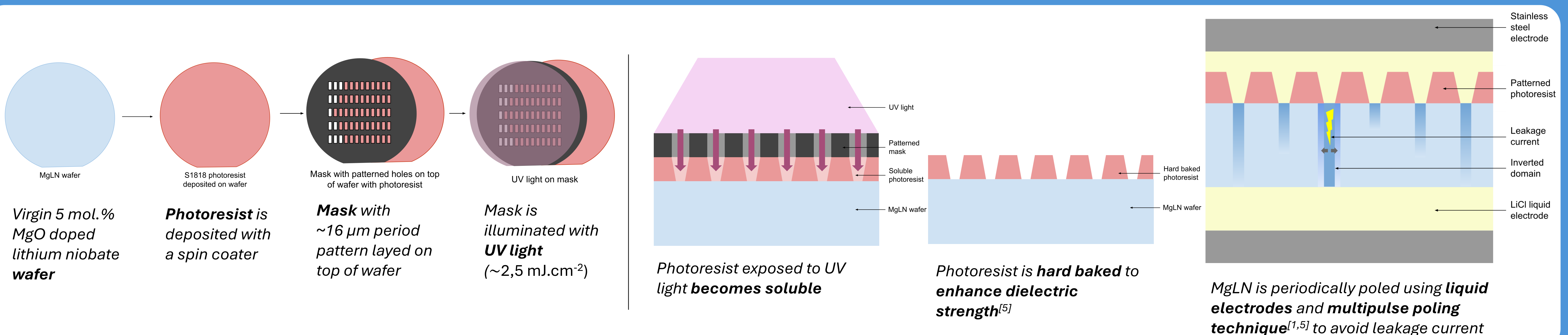
2. Advantages and disadvantages of MgO-doped Lithium niobate



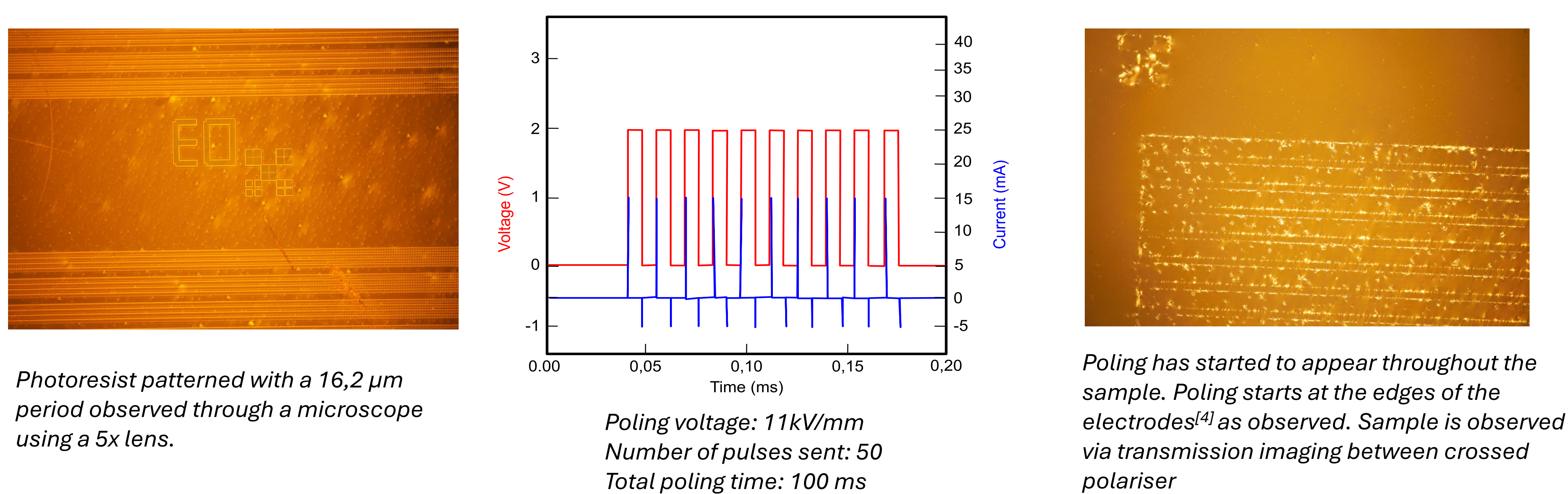
3. MgLN's behaviour while undergoing polarisation



4. Manufacturing process of periodically polarised MgO-doped lithium niobate (PPMgLN)

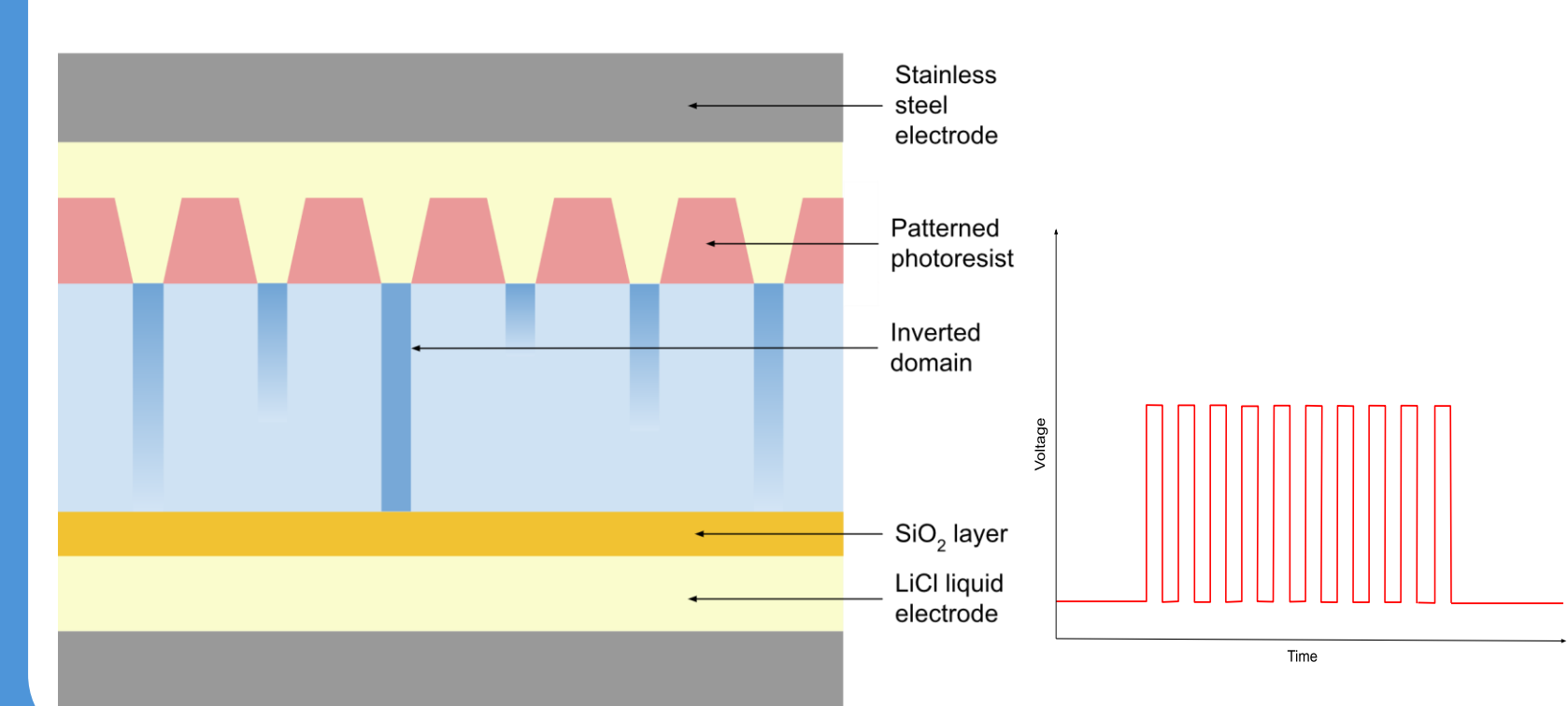


5. Observation of periodically polarised MgLN



6. Suppressing leakage current

- Deposition of a layer of SiO_2 on $-z$ face of the wafer
- Hard bake recipe after photolithography to enhance dielectric strength of photoresist
- Multipulse poling technique
- Longer poling time, spanning over several seconds



Conclusion and Perspectives

In conclusion, we have had the opportunity to investigate the poling characteristics of MgLN and have explored the new steps involved in the fabrication of PPMgLN, such as the multipulse electric-field poling method and the hard bake recipe. Furthermore, we successfully manufactured a patterned photoresist with satisfying quality with a well-established protocol. We have analysed the various factors responsible for our unsatisfactory results. The time scale dependence of the poling process in MgLN has been identified and highlights one of the parameters that need to be adjusted for PPMgLN manufacturing. The objectives for the near future is to address the limitations we have had regarding the number of pulses we were able to send and thus the poling time. Additionally, we are currently contacting neighbouring labs in order to deposit a 700 nm thick layer of silica on the MgLN wafer.

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